

AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A photomask fabrication method, wherein mask correction units are established, and

the mask correction units for photomask fabrication are corrected based on a comparison of the mask correction units with respect to actual measured variation of a manufactured structure from a desired structure,

wherein the mask correction units are comprised of a plurality of individual correction values each of which correspond to a location having a desired line width for each of a plurality of lines.

2. (Previously Presented) A photomask fabrication method according to claim 1, wherein along with correcting said mask correction units, parameter settings for lithographic equipment are corrected according to an XY differential of a resultant pattern.

3. (Previously Presented) A photomask fabricated by design data revised using mask correction units,

wherein the mask correction units are determined by measuring variation of a manufactured structure from a desired structure.

4. (Previously Presented) A photomask according to claim 3, wherein said mask correction units, are corrected in order to minimize an XY differential of a resultant pattern.

5. (Canceled) Claim 5 was previously canceled.

6. (Previously Presented) A photomask according to claim 3, wherein said mask correction units are used to minimize an XY differential of a resultant pattern with respect to a desired pattern.

7. (Previously Presented) The photomask fabrication method according to claim 1, wherein actual length measurement results are used to revise the mask correction units.

8. (Previously Presented) The photomask of claim 3, wherein actual length measurement results are used to revise the mask correction units.

9. (Currently Amended) The photomask fabrication method according to claim 1, wherein a correction grid and correction table on which optical proximity effect correction processing has been performed are utilized.

10. (Previously Presented) The photomask of claim 3, wherein a correction grid and correction table are utilized.

11. (Currently Amended) The photomask fabrication method according to claim 1, wherein if a measured average is not within less than twice absolute value of ~~the correction grid value~~ the mask correction value, the mask correction unit in ~~the correction table~~ a correction table is revised.

12. (Currently Amended) The photomask of claim 3, wherein if a measured average is not within less than twice absolute value of ~~the correction grid value~~ the mask correction value, the mask correction unit in ~~the correction table~~ a correction table is revised.

13. (Currently Amended) The photomask fabrication method according to claim 1, wherein an average of a line width in the X direction and a line width in the Y direction is determined, and if a differential between the measured value is greater than twice the absolute value of the mask correction unit, the mask correction unit in a correction table ~~the correction table~~ is revised.

14. (Currently Amended) The photomask of claim 3, wherein an average of a line width in the X direction and a line width in the Y direction is determined, and if a differential between the measured value is greater than twice the absolute value of the mask correction unit, the mask correction unit in a correction table ~~the correction table~~ is revised.